

Title (en)
Apparatus and method for anodic treatment.

Title (de)
Vorrichtung und Verfahren zur anodischen Behandlung.

Title (fr)
Appareil et procédé pour traitement anodique.

Publication
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Application
EP 86303710 A 19860515

Priority
US 73536785 A 19850517

Abstract (en)
A method for anodic surface treatment of metal surfaces comprising the steps of providing a treatment container containing a treatment solution comprising one or more of the following substances: tap water, dilute nitrate salts, dilute hydrochloric acid, dilute nitrite salts, dilute sulfuric acid, stannous and stannic salts and dilute nitric acid, positioning at least first and second electrodes in the treatment container, applying AC electrical current across the electrodes and causing a metal element to be located in the treatment container during application of the AC electrical current across the electrodes. DC surface treatment is also described.

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Citation (search report)
• US 4448475 A 19840515 - REZNICK DAVID [IL]
• DE 2646697 A1 19770428 - NAT STEEL CORP
• DE 1496808 A1 19700910 - GEN DYNAMICS CORP
• PATENT ABSTRACTS OF JAPAN, unexamined applications, C field, vol. 8, no. 193, September 5, 1984 THE PATENT OFFICE JAPANESE GOVERNMENT page 94 C 241 * JP-A 59 85 893 (SHIN NIPPON SEITETSU K.K.) *

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